



Session Title	Atomic Layer Deposition for Emerging Applications II	Session Code	Fr-C2
Date and Time	2018-08-24 / 10:45 - 12:45		
Place	Room C		
Session Chair	TBA		

Fr-C2-1

10:45 - 11:15

[Invited]Atomic Layer Deposition for Solar Fuels

Jihun Oh
KAIST, Korea

Fr-C2-2

11:15 - 11:45

[Invited]Two-Dimensional Electron Gas at Oxide Heterostructures using Atomic Layer Deposition

Sang Woon Lee
Ajou Univ., Korea

Fr-C2-3

11:45 - 12:15

[Invited]Atomic Layer Deposition; A Few Prospective Applications Aiming Mass-Production after Si-based Semiconductor Process Era

Tae Joo Park
Hanyang Univ., Korea

Fr-C2-4

12:15 - 12:30

Atomic Layer Deposited Transition Metal Sulfide and Nitride for Energy Storage Application

Dip K. Nandi¹, Tae Hyun Kim¹, M. Zahid Ansari¹, Seungmin Yeo², Hyungjun Kim², and Soo-Hyun Kim²
¹Yeungnam Univ., Korea, ²Yonsei Univ., Korea

Fr-C2-5

12:30 - 12:45

Low-Temperature ALD Cobalt Sulfide for Efficient Hydrogen Evolution Reaction Catalyst based on Textiles

Hyungjun Kim, Donghyun Kim, and Jusang Park
Yonsei Univ., Korea

Fr-C2-6

12:45 - 13:00

***In-Situ* Synthesis of Vertically Stacked Heterostructure WSe₂/WS₂ for Photovoltaic Self-Powered Gas Sensor**

Sangyoon Lee, KyungYong Ko, Jusang Park, and Hyungjun Kim
Yonsei Univ., Korea